Wednesday Morning, November 1, 2017

2D Materials Focus Topic
Room 15 - Session 2D+EM+SS+TF-WeM

2D Materials Growth and Fabrication

Moderator: Aleksandra Radenovic, Ecole Polytechnique Fédérale de Lausanne (EPFL), Switzerland

8:00am 2D+EM+SS+TF-WeM-1 Chemical Bath Deposition of Phase Selective MoS₂ on Templated Surfaces, *Jenny Hedlund, A Walker,* University of Texas at Dallas

Transition metal dichalcogenides (TMDs) have a wide range of physical properties, and consequently have applications in nanoelectronics and biosensors. While TMD materials have been well studied, a simple method for two-dimensional large area thin film deposition of these materials has yet to be achieved. Chemical bath deposition (CBD) is a robust method by which to grow uniform thin films, and offers many advantages over other techniques including low deposition temperatures (≤ 50°C), synthetic flexibility, and it is inexpensive. In this work, CBD is used to deposit large-area ultra-thin molybdenum disulfide (MoS₂), a group VI TMD, and the resulting deposits are investigated by scanning electron microscopy (SEM), x-ray photoelectron spectroscopy (XPS), Raman spectroscopy and time-of-flight secondary ion mass spectrometry (TOF SIMS). These TMDs are most commonly found to possess trigonal prismatic crystalline structure (2H phase) and therefore are semiconductors. Although less widely studied, TMDs can also possess octahedral crystallinity to form the 1T phase. The 1T phase exhibits different properties to the 2H phase, and has applications in sensing, metal contacts and catalysis. By using substrates that mimic the TMD crystalline structure for deposition we have shown that MoS₂ can be deposited with large-area crystallites observed. SEM images of deposition performed on highly oriented pyrolytic graphite show large area flakes, ~100 μm in diameter. Smooth thin films were also deposited on sapphire, and functionalized self-assembled monolayers (SAMs). XPS results show that Mo 3d and S 2s peaks are present in the expected positions and ratios. We further demonstrate that the deposited MoS₂ phase is likely determined by the surface chemistry of the substrate. Using Raman spectroscopy measurements, the thickness and phase of the film are elucidated. CBD of MoS₂ was further characterized using TOF SIMS to elucidate the reaction mechanisms as well as the stability of the deposited film.

8:20am 2D+EM+SS+TF-WeM-2 Atomic Layer and Metalorganic Chemical Vapor Deposition of MoS₂ and WS₂ from bis(tert-butylimido)-bis(dialkylamido) Compounds, *Berc Kalanyan, J Maslar, W Kimes, B Sperling,* NIST*; R Kanjolia,* EMD Performance Materials

Layered 2D transition-metal dichalcogenides (TMDs) are finding use in nanoelectronic and optoelectronic applications due to their thickness-dependent optical and electrical properties. Scalable fabrication of TMD-based devices requires vapor-phase deposition routes that can produce continuous and uniform films with sub-nanometer thickness control. Atomic layer deposition (ALD) is a desirable route for the synthesis of 2D TMDs and heterostructures due to digital thickness control achieved by sequential self-limiting surface chemistry. However, since ALD conditions are only met at relatively low deposition temperatures, most ALD films are amorphous. Some consider this a useful feature of ALD, since film growth rate and structural development can be decoupled by separating the deposition and crystallization steps. In contrast, metalorganic chemical vapor deposition (MOCVD) enables direct growth of crystalline films, but requires careful process control and precursor selection to achieve the required level of thickness control. The tradeoffs between direct CVD growth and post-sufurization and annealing of amorphous/metallic films is the focus of this work.

In this paper, we present a comparison of process characteristics and film properties, including growth rate, thickness, morphology, composition, and crystallinity, as a function of two deposition routes: ALD and MOCVD. We deposited thin films using (NᵗBu)₂(NMe₂)₂M and 1-propanethiol, where M={Mo,W}, at wafer temperatures of 200°C to 400°C for ALD and 400°C to 900°C for pulsed MOCVD on SiO₂/Si substrates. Precursor saturation conditions were evaluated using in situ infrared flow measurements and ex situ X-ray photoelectron spectroscopy. As-deposited and sulfur-annealed films were further evaluated using X-ray diffraction, optical spectroscopies, and microscopy. As-grown ALD films were amorphous and included a mixture of a sulfide and a conductive phase, likely a nitride. Below 300°C, deposition was limited to a thin surface oxide. Higher temperatures resulted in higher growth rates, which also introduced a weak CVD component to the growth. Deposition rates were <1.0 Å/cycle at 350°C. As-

deposited films were successfully annealed to 2H-MoS₂ under a sulfur atmosphere, which also removed residual nitrogen. As-grown MOCVD films were polycrystalline 2H-MoS₂ at 600°C. Pulsed injections of precursor enabled Å-level control over aggregate film thickness. For both processes, wafer-scale growth and uniformity in a perpendicular flow reactor were demonstrated on 50 mm substrates. We will also present process characteristics for the analogous WS₂ route and discuss initial data from MoS₂/WS₂ nanolaminates.

8:40am 2D+EM+SS+TF-WeM-3 Epitaxial Growth of Atomically Thin Transition Metal Dichalcogenides and their Electronic Structures, *Sung-Kwan Mo,* Lawrence Berkeley National Laboratory **INVITED**

Transition metal dichalcogenides (TMDCs) is a versatile material platform with a variety of electrical, optical, and topological properties that can be controlled through thickness, strain, field, and other perturbations. In this talk, I will first discuss the growth of atomically-thin TMDC films, such as MoSe₂, WSe₂, WTe₂, NbSe₂, and TaSe₂, with a layer-by-layer thickness control, using molecular beam epitaxy. Then, I will present how we investigate the electronic structures of these films using angle-resolved photoemission spectroscopy and scanning tunneling microscopy.

9:20am 2D+EM+SS+TF-WeM-5 Terminations and Treatments of Silicon Carbide Surfaces to Promote Epitaxial Hexagonal Boron Nitride Deposition by Chemical Beam Epitaxy, *Daniel Pennachio, N Wilson, A McFadden, T Brown-Heft,* University of California at Santa Barbara*; K Daniels, R Myers-Ward, D Gaskill, C Eddy, Jr.,* U.S. Naval Research Laboratory*; C Palmstrøm,* University of California at Santa Barbara

This work examines the epitaxial deposition of single-crystal hexagonal boron nitride (h-BN) on silicon carbide substrates through the use of surface treatments which promote suitable nucleation and growth. Silicon carbide, 6H-SiC(0001), was chosen as a candidate substrate due to its market availability, high crystalline quality, temperature stability, and potential coincident lattice match to h-BN. Boron nitride was deposited in ultra-high vacuum (UHV) environments by chemical beam epitaxy (CBE) on SiC substrates through thermal decomposition of borazine at high temperatures. Different SiC surface reconstructions reached through exposure to elemental silicon and subsequent *in-vacuo* annealing were examined for their effect on h-BN nucleation and epitaxial arrangement. Along with reconstructions produced through UHV annealing, CVD-grown epitaxial graphene on 4H-SiC was also utilized as a growth surface. Growth past full single atomic layer coverage of sp²-bonded material (either h-BN deposited layers or graphene substrates) proved difficult with the accessible temperature range and precursor flux. Various surface treatment approaches were investigated to promote additional layer growth.

Deposited h-BN films on the SiC reconstructed surfaces were found to be near-stoichiometric and of single- to few-atomic layer thickness, as determined by *in-situ* x-ray photoelectron spectroscopy (XPS) B1s:N1s peak area ratios and substrate peak attenuation. Progression of *in-situ* reflection high-energy electron diffraction (RHEED) during h-BN deposition provides evidence of a difference in film nucleation between the Si-rich (3x3) and the C-rich SiC surface reconstructions: while the (3x3) reconstruction quickly transitioned to a (1x1) reconstruction upon precursor dosing, the C-rich reconstruction persisted despite thicker depositions. XPS of the C-rich surface showed a higher binding energy shoulder of the C1s peak, indicative of sp²-hybridized bonding in a graphene-like buffer layer at the surface. Triangular nuclei seen by scanning electron microscopy after deposition on the C-rich SiC surface suggests epitaxial arrangement to this buffer layer. *In-situ* scanning probe microscopy and *ex-situ* transmission electron microscopy were performed to acquire additional information on film morphology. The influence of different surface treatments for increasing the thickness of h-BN growth will be presented.

9:40am 2D+EM+SS+TF-WeM-6 Photo-Chemical Modification of Monolayer Transition Metal Dichalcogenides, *Tariq Afaneh, P Sahoo, H Gutierrez,* University of South Florida

Fabrication of in-plane 2D heterostructures is a crucial step to advance in the development of a truly 2D optoelectronics. Different approaches have been attempted, including in situ sequential growth of two different materials and post-growth modification of the chemical composition in a 2D monolayer. In this work, we studied a post-growth technique that exploits the radiation-matter interaction under a controlled atmosphere. Using a homemade sealed mini-chamber with a quartz optical viewport, a laser beam (532 nm) was focused onto the sample, consisting on MoSe₂ or WSe₂, while keeping a reactive sulfur-rich atmosphere within the chamber. The spatially localized photo-chemical conversion was in situ monitored by

mapping the temporal evolution of the Raman active modes. The process can be tuned thereby choosing appropriate laser power, exposure time, and reactive gas environment. The complete or partial conversion was further confirmed by collecting the photoluminescence spectra at the desired exposed sites. The time-dependent intensities of the Raman peaks were fitted to exponentially decaying functions. Depending on the reaction parameters, two different processes with distinct time constants can be identified. The following mechanisms for the photo-conversion are proposed: (i) creation of Se vacancies in the TMD materials due to the energy absorbed from the laser radiation, (ii) cracking of sulfur containing molecules from the gas environment and subsequent incorporation of the sulfur atoms into the Se vacancy sites. The optimization of this process will allow to develop techniques based on photo-induced chemical reactions for local doping, alloying and the fabrication of in-plane TMD heterostructure.

11:00am **2D+EM+SS+TF-WeM-10 Bottom-up synthesis of Graphene Nanomembranes with Tunable Porosity**, *Christof Neumann,* Friedrich Schiller University Jena, Germany*; M Füser,* Goethe University Frankfurt, Germany*; M Mohn,* Ulm University, Germany*; D Kaiser,* Friedrich Schiller University Jena, Germany*; A Gölzhäuser,* Bielefeld University, Germany*; U Kaiser,* Ulm University, Germany*; A Terfort,* Goethe University Frankfurt, Germany*; A Turchanin,* Friedrich Schiller University Jena, Germany

The potential of atomically thin materials like graphene or carbon nanomembranes (CNMs) [1] for separation or ultrafiltration technologies is based on their negligible thicknesses enabling the ballistic transport of atoms and molecules through the nanomembranes. For such implementations, large scale production of perforated nanomembranes with well-defined sizes of nanopores has to be established. Here we present a scalable method to produce atomically thin graphene nanomembranes with tunable porosity using aromatic self-assembled monolayers (SAMs) as molecular precursors. We employ N-containing 4-(1H-pyrrol-1-yl)thiophenol, 4-(2,5-dimethyl-1H-pyrrol-1-yl)thiophenol and 4-(pyrimidin-2-yl)phenylthiol SAMs on polycrystalline copper foils to convert them into CNMs via low energy electron irradiation induced crosslinking and then to pyrolyze CNMs into nanoporous graphene sheets in vacuum. We characterize the formed supported and suspended graphene nanosheets by different complementary spectroscopy and microscopy techniques including X-ray photoelectron (XPS) and Raman spectroscopy, atomic force (AFM), helium ion (HIM) and high-resolution transmission electron microscopy (HRTEM) as well as by electric transport measurements. We demonstrate that the pore size and the graphene crystallinity can be adjusted by the production parameters and discuss the mechanisms.

[1] A. Turchanin and A. Gölzhäuser, Carbon Nanomembranes, *Adv. Mater.* 28 (2016) 5075

11:20am **2D+EM+SS+TF-WeM-11 Cu Single Crystal Substrates for Growth of CVD Graphene**, *Tyler Mowll,* University at Albany, SUNY*; Z Robinson,* SUNY Brockport*; C Ventrice, Jr.,* SUNY Polytechnic Institute

To provide a systematic study of the CVD graphene growth process, a study of the growth of graphene on single crystal Cu substrates, with terminations along the (100), (110), and (111) planes, was performed. Synthesis was performed in an ultra-high vacuum (UHV) chamber using a modified setup to allow growth at pressures as high as 1 Torr. Ethylene was used as the precursor gas. To control Cu sublimation at the elevated growth temperatures, an Ar overpressure was used. This arrangement allowed for the preparation of clean Cu surfaces by sputtering and annealing the Cu crystals in UHV, followed by graphene growth at low pressure, and in-situ analysis with low energy electron diffraction. It was found that surface termination plays a strong role in the rotational alignment of the nucleating graphene grains and the decomposition rate of the ethylene. It was observed that single-domain epitaxy is possible on Cu(111) when the ethylene pressure is 5 mTorr or less. However, growth on both Cu(100) and Cu(110) result in a minimum of two domains. In addition, ex-situ EELS is currently being performed on well-ordered epitaxial graphene films grown on Cu(111) and Cu(100) to determine the effect of the graphene-Cu interaction on the electronic properties of the graphene.

11:40am **2D+EM+SS+TF-WeM-12 Paper and Circuits, only Atoms Thick**, *Jiwoong Park,* University of Chicago **INVITED**

2D layered materials are like paper: they can be colored, stitched, stacked, and folded to form integrated devices with atomic thickness. In this talk, I will discuss how different 2D materials can be grown with distinct electrical and optical properties (coloring), how they can be connected laterally to form pattered circuits (stitching), and how their properties can be controlled by the interlayer rotation (twisting). We will then discuss how these atomically thin papers and circuits can be folded to generate active 3D systems.

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